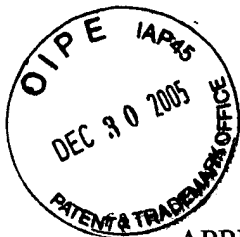


Handwritten signature/initials in the top right corner.

PATENT



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

APPLICANTS: Yi Yeol LYU et al. CONF. NO.: 8277
SERIAL NO.: 10/722,460 GROUP: 2818
FILED: November 28, 2003 EXAMINER: Quoc Dinh Hoang
FOR: SILOXANE-BASED RESIN AND A SEMICONDUCTOR
INTERLAYER INSULATING FILM USING THE SAME
DOCKET NO.: 6661-000007/US

RESPONSE TO RESTRICTION REQUIREMENT

Customer Service Window
Randolph Building
401 Dulany Street
Alexandria, VA 22314
Mail Stop Amendment

December 30, 2005

Dear Sir:

Responsive to the Examiner's Restriction Requirement dated October 31, 2005, the due date having been extended one (1) month to December 31, 2005, the following remarks are respectfully submitted in connection with the above-referenced application.

01/03/2006 MBEYENE1 00000021 10722460

01 FC:1251

120.00 DP

REMARKS

The Examiner required restriction of one of the following inventions:

Group I: claims 1-8 and 16-18, drawn to a siloxane-based resin, classified in class 257, subclass 643; and